

Title (en)

Complementary semiconductor device comprising two heterostructure field-effect transistors with strained channel layer

Title (de)

Komplementäre Halbleiteranordnung mit zwei Heterostruktur-Feldeffekttransistoren mit verspannter Kanalschicht

Title (fr)

Dispositif semi-conducteur complémentaire comprenant deux transistors à effet de champ à hétérostructure et couche de canal contrainte

Publication

**EP 0921575 A2 19990609 (EN)**

Application

**EP 98122863 A 19981202**

Priority

JP 33272697 A 19971203

Abstract (en)

A MISFET having extremely high mobility comprising a first silicon layer (Si layer)(12), a silicon layer containing carbon (Si1-yCy layer)(13) and an optional, second silicon layer (Si layer)(14) stacked in this order on a silicon substrate (10). The carbon content and thickness of the Si1-yCy layer acting as a channel layer of the MISFET are such that said Si1-yCy layer is under tensile strain whereby the conduction and valence bands thereof are split. Therefore, charge carriers having a smaller effective mass, which have been induced by an electric field applied to an insulated gate electrode (15,16), are confined in the Si1-yCy layer, and move in the channel direction. Furthermore, if the silicon layer containing carbon is made of Si1-x-yGexCy, a structure suitable for a high-performance CMOS device can be formed. Alternatively, the silicon layers may contain a slight amount of carbon or germanium, and a Schottky gate may be provided whereby a MESFET is achieved. <IMAGE>

IPC 1-7

**H01L 29/778**; **H01L 29/78**; **H01L 29/165**; **H01L 29/161**

IPC 8 full level

**H01L 21/338** (2006.01); **H01L 21/762** (2006.01); **H01L 29/10** (2006.01); **H01L 29/161** (2006.01); **H01L 29/778** (2006.01); **H01L 29/78** (2006.01); **H01L 29/80** (2006.01); **H01L 29/812** (2006.01)

CPC (source: EP KR US)

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DOCDB simple family (application)

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